

INFORMATION DISCLOSURE CITATION PTO-1449			Atty. Docket No. NMTI 1002-9		Serial No. 10/068,513-3666	
			Applicant PIERRAT, Christophe			
			Filing Date 2/6/2002		Group 1756	
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EXAMINER'S INITIALS	PATENT NO.	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
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SRM	JP 6-67403	3/11/1994	JP	—	—	<input checked="" type="checkbox"/>	<input type="checkbox"/>
SRM	WO 01/23961 A1	4/5/2001	WO	—	—	<input type="checkbox"/>	<input type="checkbox"/>
SRM	JP 1,283,925	2/14/1991	JP	—	—	<input checked="" type="checkbox"/>	<input type="checkbox"/>
SRM	WO 02/03140 A1	1/10/2002	WO	—	—	<input type="checkbox"/>	<input type="checkbox"/>
SRM	JP 2-140743	5/30/1990	JP	—	—	<input checked="" type="checkbox"/>	<input type="checkbox"/>
SRM	GB 2,333,613 A	7/28/1999	GB	—	—	<input type="checkbox"/>	<input type="checkbox"/>
SRM	JP 2,638,561	4/25/1997	JP	—	—	<input type="checkbox"/>	<input type="checkbox"/>
SRM	JP 2,650,962	5/16/1997	JP	—	—	<input type="checkbox"/>	<input type="checkbox"/>
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SRM	JP 8,051,068	2/20/1996	JP	—	—	<input checked="" type="checkbox"/>	<input type="checkbox"/>
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SRM	JP 11-143085	5/28/1999	JP	—	—	<input type="checkbox"/>	<input type="checkbox"/>
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SHEET 1 of 2

INFORMATION DISCLOSURE CITATION PTO-1449	Atty. Docket No.	Serial No.
	NMTI 1002-9	10/068,513
	Applicant	
	PIERRAT, Christophe	
	Filing Date	Group
	2/6/2002	1756

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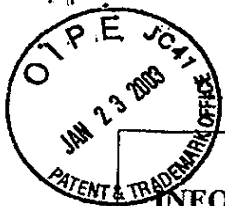
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EXAMINER'S INITIALS	PATENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE
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SHEET 2 of 2

INFORMATION DISCLOSURE CITATION PTO-1449		Atty. Docket No. NMTJ 1002-9 Applicant PIERRAT, Christophe Filing Date 2/6/2002	Serial No. 10/068,513 Group 1756
OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)			
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